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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/594,840	05/20/2008	Masaaki Yokoyama	Q97512	3659
23373 7590 01/18/2012 SUGHRUE MION, PLLC 2100 PENNSYLVANIA AVENUE, N.W.			EXAMINER	
			KHAN, TAHSEEN	
SUITE 800 WASHINGTO	ON. DC 20037	ART UNIT	PAPER NUMBER	
	, - 0		1783	
			NOTIFICATION DATE	DELIVERY MODE
			01/18/2012	ELECTRONIC

## Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

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# Office Action Summary

Application No.	Applicant(s)	Applicant(s)					
10/594,840	YOKOYAMA ET AL.	YOKOYAMA ET AL.					
Examiner	Art Unit						
TAHSEEN N. KHAN	1783						

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The MAILING DATE of this communication appears on the cover sheet with the correspondence address							
Period for Reply  A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA  Extensions of man may be available under the provisions of 37 GPR 1.1s after SIX (6) MOX1175 from the mailing date of the somerunication.  If NO period for reply is specified above, the maximum statutory period of Failure or criply within the sort extended profiled or reply will. She shill.  Any reply received by the Office later than three montains after the mailing aeried patent term adjustment. See 37 GPR 1.79(4b).	ATE OF THIS COMMUNICATION 8(a). In no event, however, may a reply be tim fill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE!	I. sely filed the mailing date of this of 0 (35 U.S.C. § 133).					
Status							
1) Responsive to communication(s) filed on 28 Dec. 2a) This action is FINAL. 2b) This 3) An election was made by the applicant in responsive for the restriction requirement and election. 4) Since this application is in condition for allower closed in accordance with the practice under Expression.	action is non-final.  onse to a restriction requirement shave been incorporated into this nee except for formal matters, pro	action. secution as to the					
Disposition of Claims							
5) ☐ Claim(s) 1-16 is/are pending in the application.  5a) Of the above claim(s) 14-16 is/are withdraw 6) ☐ Claim(s) is/are allowed. 7) ☐ Claim(s) is/are rejected. 8) ☐ Claim(s) is/are objected to. 9) ☐ Claim(s) are subject to restriction and/or	n from consideration.						
Application Papers							
10) ☐ The specification is objected to by the Examinei 11) ☐ The drawing(s) filed on is/arc: a) ☐ accc Applicant may not request that any objection to the c Replacement drawing sheet(s) including the correct	epted or b) objected to by the Edrawing(s) be held in abeyance. See ion is required if the drawing(s) is obj	a 37 CFR 1.85(a). ected to. See 37 C					
Priority under 35 U.S.C. § 119							
13) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of:  1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the prior	s have been received. s have been received in Applicati- ity documents have been received (PCT Rule 17.2(a)).	on No ed in this National	Stage				
Attachment(s)							
1) Notice of References Cited (PTO-892)	Interview Summary     Paper No(s)/Mail Da						

Attachment(s)		
Notice of References Cited (PTO-892)     Notice of Draftsperson's Patent Drawing Review (PTO-948)	Interview Summary (PTO-413)     Paper No(s)/Mail Date	
Information Displaceure Statement(s) (PTO/SE/03)     Paper No(s)/Mail Date	5) Notice of Informal Patent Application  6) Other:	

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#### DETAILED ACTION

1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 12/2/2011 has been entered.

## Response to Amendment

 The amendment filed on Applicant's arguments filed on 12/28/2011 is acknowledged. Claim 1 has been amended. Claims 14-16 are withdrawn.

## Claim Rejections - 35 USC § 103

- The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. The factual inquiries set forth in *Graham* v. John Deere Co., 383 U.S. 1, 148 USPQ 459 (1966), that are applied for establishing a background for determining obviousness under 35 U.S.C. 103(a) are summarized as follows:
  - Determining the scope and contents of the prior art.
  - Ascertaining the differences between the prior art and the claims at issue.
  - Resolving the level of ordinary skill in the pertinent art.
  - Considering objective evidence present in the application indicating obviousness or nonobviousness.

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 Claims 1-10, 12, and 13 are rejected under 5 U.S.C. 103(a) as obvious over Kobayashi JP\_2004/071473\_A (see Machine English Translation) in view of Kajiura USPN 5,907,382 and Hiraoka USPA\_20030107465\_A1.

6. Regarding claims 1-10 and 12-13, *Kobayashi* discloses forming a **pattern** (Title) on a substrate whereon the substrate has a wettability variable layer [element 3 in Figures 1-6 and Abstract; corresponds to claimed forming layer (B)]. Kobayashi further discloses that its wettability variable layer [aka "wettability -- strange -- voltinism -- the layer", element 3 in Figures 1-6; corresponds to claimed forming layer (B)] can be comprised of an organic polysilane, as starting monomers, that are irradiated to form organopolysiloxanes (paragraphs 0028-0032, and 0086). Kobayashi also discloses that part of its wettability variable layer [aka "wettability -- strange -- voltinism -- the layer". element 3 in Figures 1-6; corresponds to claimed forming layer (B)1 can be irradiated by UV light via a mask to form high-wettability irradiated portions (element 3A in Figures 4-6) on its layer (Abstract and paragraphs 0016, 0038, 0087). Kobayashi additionally discloses applying a solution [aka "coating liquid"; element 10 in Figure 4) comprised of a hydrophilic solvent (paragraphs 0049, 0055, and 0080), water (paragraph 0055), and polymers such as polyanilines (paragraph 0052) and polythiophenes (paragraph 0088) to form a layer [element 10' in Figures 4-7; corresponds to claimed layer (C)] over at least the irradiated portions. Since Kobayashi discloses having electrodes and known conductive oxides like ITO (paragraph 0068) on its substrate, it would therefore be analogous to the claimed conductive substrate (A). Lastly, Kobayashi discloses that

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its patterned substrate can be used in **organic devices**, **organic transistors**, **organic solar cells**, **organic electroluminescense devices**, etc. (paragraph 0004).

- 7. However, Kobayashi does NOT explicitly disclose the following limitations:
- using radiation to oxidize its starting material of organic polysilanes,
- impregnating its wettability variable layer [aka "wettability -- strange -- voltinism -- the layer", element 3 in Figures 1-6; corresponds to claimed forming layer (B)] with its conducting organic polysilanes, and
- applying a solution of its conductive polymer to the "whole area" of its wettability variable layer [aka "wettability -- strange -- voltinism -- the layer", element 3 in Figures 1-6; corresponds to claimed forming layer (B)].
- 8. Kajiura discloses irradiating a polysilane thin film which results in photo-oxidation that produces a polysiloxane thin film that is subsequently placed on a substrate (column 12, lines 43-53). Kajiura further discloses impregnating its polysilane thin film layer as well with conductive silane coupling agents (column 15, lines 44-56). Kajiura discloses using its substrate and polysilane thin film in applications such as EL displays (column 16, lines 13-29) to provide a transparent conductive substrate having a base with both heat resisting characteristic and optical characteristics. Kajiura further discloses that its invention can provide a transparent conductive substrate with a scratch resisting characteristic, an oxygen barrier characteristic, a steam barrier characteristic, and adhesion of a transparent electrode layer; wherein the substrate can be used to provide a small, thin, and light display apparatus having the above-described transparent conductive substrate (column 3, lines 9-20).

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9. It would have been obvious to one of ordinary skill in the art at the time the invention was made to modify the process, of *Kobayashi*, by irradiating its organic polysilane starting materials to oxidize them into organic polysiloxanes and to subsequently impregnate its conductive layer with silanols, as is exemplified by *Kajiura*. One of ordinary skill in the art would have been motivated in doing so in order to obtain the benefits of *Kajiura's* transparent conductive substrate such as its scratch resisting characteristic, an oxygen barrier characteristic, a steam barrier characteristic, and adhesion of a transparent electrode layer.

- 10. Hiraoka discloses forming a substrate for electric and communication fields (paragraph 0002); wherein a conductive pattern can be made (paragraph 0050). Hiraoka further discloses that it is known in prior art to use solutions of conductive polymers having a hydrophilic solvent and then immersing the irradiated sheets into it in order for the conductive polymer to impregnate the entire sheet including the irradiated portions (paragraph 0064). Hiraoka further exemplifies doing this in its Examples (paragraph 501). Hiraoka further discloses that its method helps in freeing its invention from problems such as layer peeling (Abstract).
- 11. It would have been obvious to one of ordinary skill in the art at the time the invention was made to modify the wetting layer, of *Kobayashi*, by immersing it in its conductive polymer solution entirely, as exemplified by *Hiraoka*. One of ordinary skill in the art would have been motivated in doing so in order to prevent peeling in its invention as disclosed above by *Hiraoka*.

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12. Alternatively, Regarding claims 1-7, the processes of forming the patterned substrate disclosed in claims 1-7 are not essential to a determination of patentability of the composition disclosed in the claim. The patentability of product-by-process claims is based on the product itself. "[E]ven though product-by-process claims are limited by and defined by the process; determination of patentability is based on the product itself. The patentability of a product does not depend on its method of production. If the product in the product-by-process claim is the same as or obvious from a product of the prior art, the claim is unpatentable even though the prior product was made by a different process." In re Thorpe, 777 F.2d 695, 698, 227 USPQ 964, 966 (Fed. Cir. 1985). See MPEP 2113. The examiner respectfully submits that none of the limitations claimed in claims 1-7 by applicants impart a structural property in the end product of their claimed patterned substrate. The examiner has shown above that processes utilized by the motivated combination of, *Kobayashi* in view of *Kajiura*, implies all of the nuances of the claimed processes.

- 13. Claim 11 is rejected under 35 U.S.C. 103(a) as being unpatentable over *Kobayashi* JP\_2004/071473\_A (see Machine English Translation) in view of *Kajiura* USPN 5,907,382 and *Hiraoka* USPA\_20030107465\_A1, as applied to claim 1, and further in view of *Veres* WO 2004/013922 A2.
- 14. Regarding claim 11, Kobayashi in view of Kujiara suggests that its patterned substrate can be used to form organic devices, organic transistors, organic solar cells, organic electroluminescense devices, etc. (paragraph 0004). However, the combination does not disclose forming photosensors.

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15. Veres discloses forming a pattern on a substrate that can be used in organic electronic devices such as organic solar cells and organic photosensors (Abstract).

16. It would have been obvious to one of ordinary skill in the art to use the patterned substrate, of *Kobayashi*, for devices such as photosensors as exemplified by *Veres*. One of ordinary skill in the art would have been motivated in doing so due to the analogous subject matter as well as the fact that *Veres* uses its patterned substrate in organic solar cells, as does *Kobayashi*.

### Response to Arguments

17. Applicant's arguments with respect to all elected claims have been considered but are moot in view of the new ground(s) of rejection.

### CONCLUSION

- 18. Any inquiry concerning this communication or earlier communications from the examiner should be directed to TAHSEEN KHAN whose telephone number is (571)270-1140. The examiner can normally be reached on Monday to Thursday from 7:30am-5:30pm EST.
- 19. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David R. Sample can be reached on (571)272-1376. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.
- 20. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only.

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/T.N.K./ TAHSEEN N. KHAN Patent Examiner, Art Unit 1783 January 10, 2012

/Angela Ortiz/

Supervisory Patent Examiner, Art Unit 1798